

ABSTRACT

METHOD AND APPARATUS FOR CLEANING A SEMICONDUCTOR
WAFER PROCESSING SYSTEM

A method and apparatus for cleaning a semiconductor wafer processing system comprising a turbomolecular pump.

5 In one embodiment, the invention may be reduced to practice by first supplying a cleaning agent to a chamber; pumping the cleaning agent from the chamber through an the exhaust port; at least partially opening a gate valve; and drawing at least a portion of the cleaning agent through the gate.

10 valve and into the turbomolecular pump.

Fig. 1